

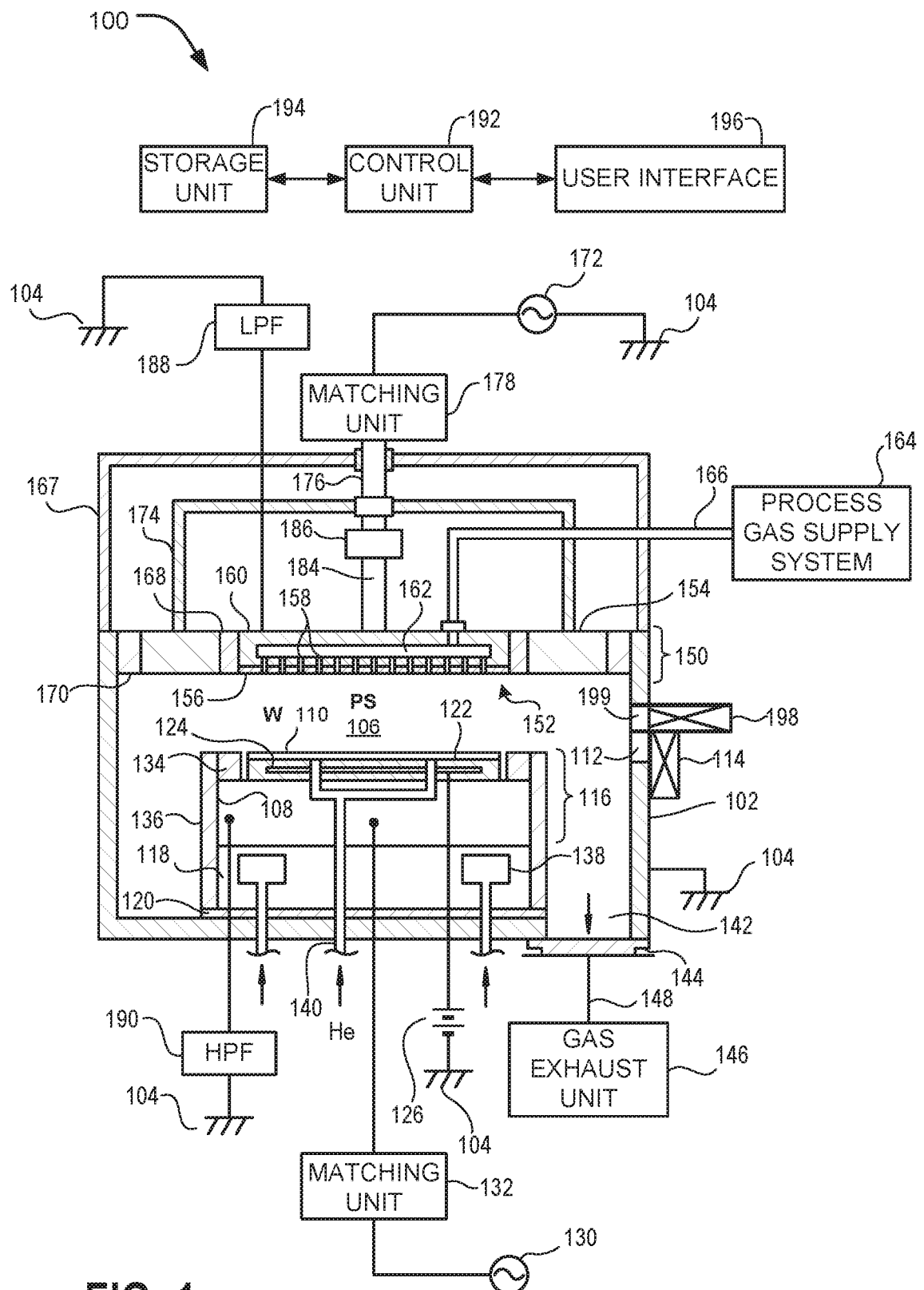


FIG. 1

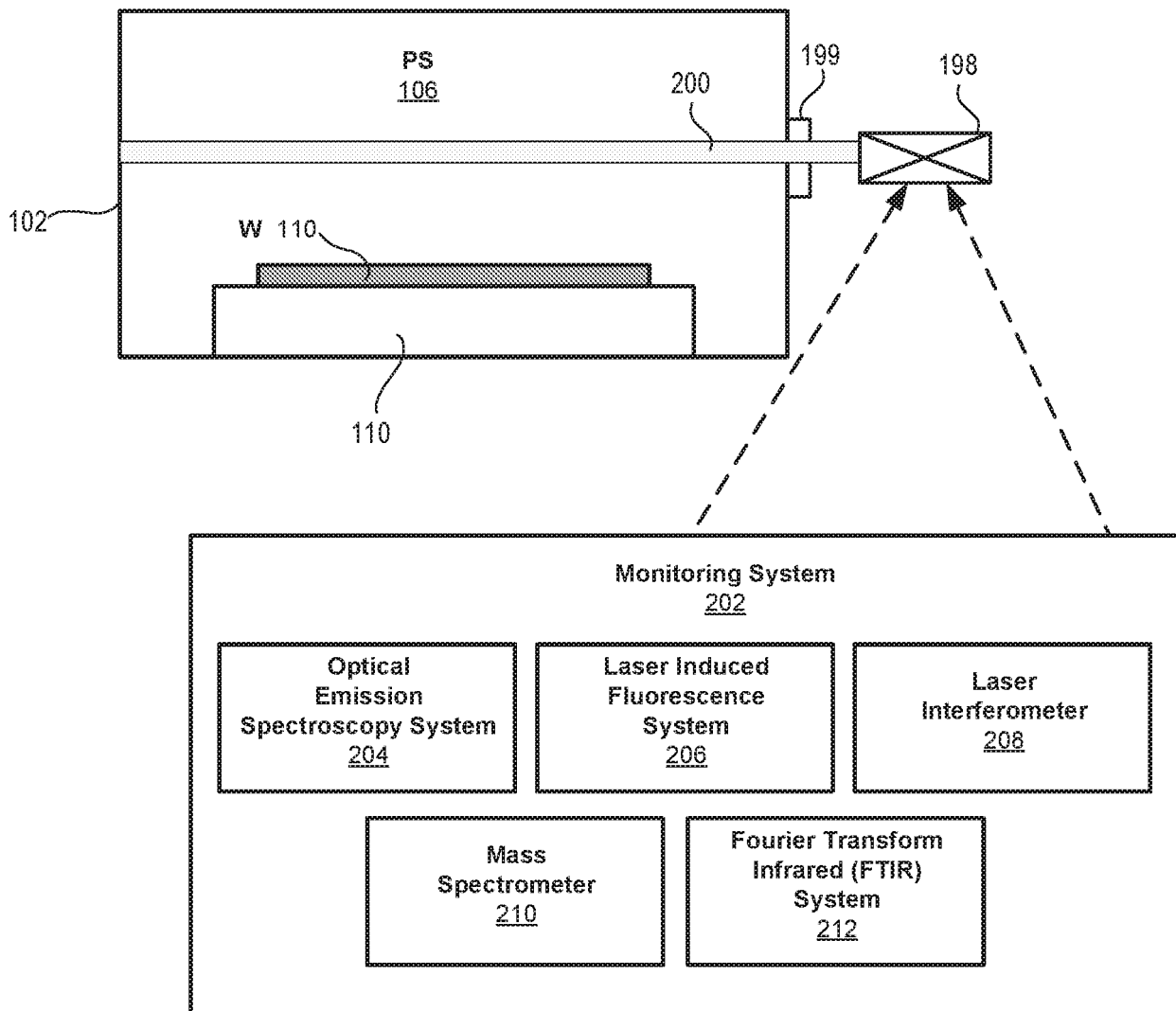


FIG. 2

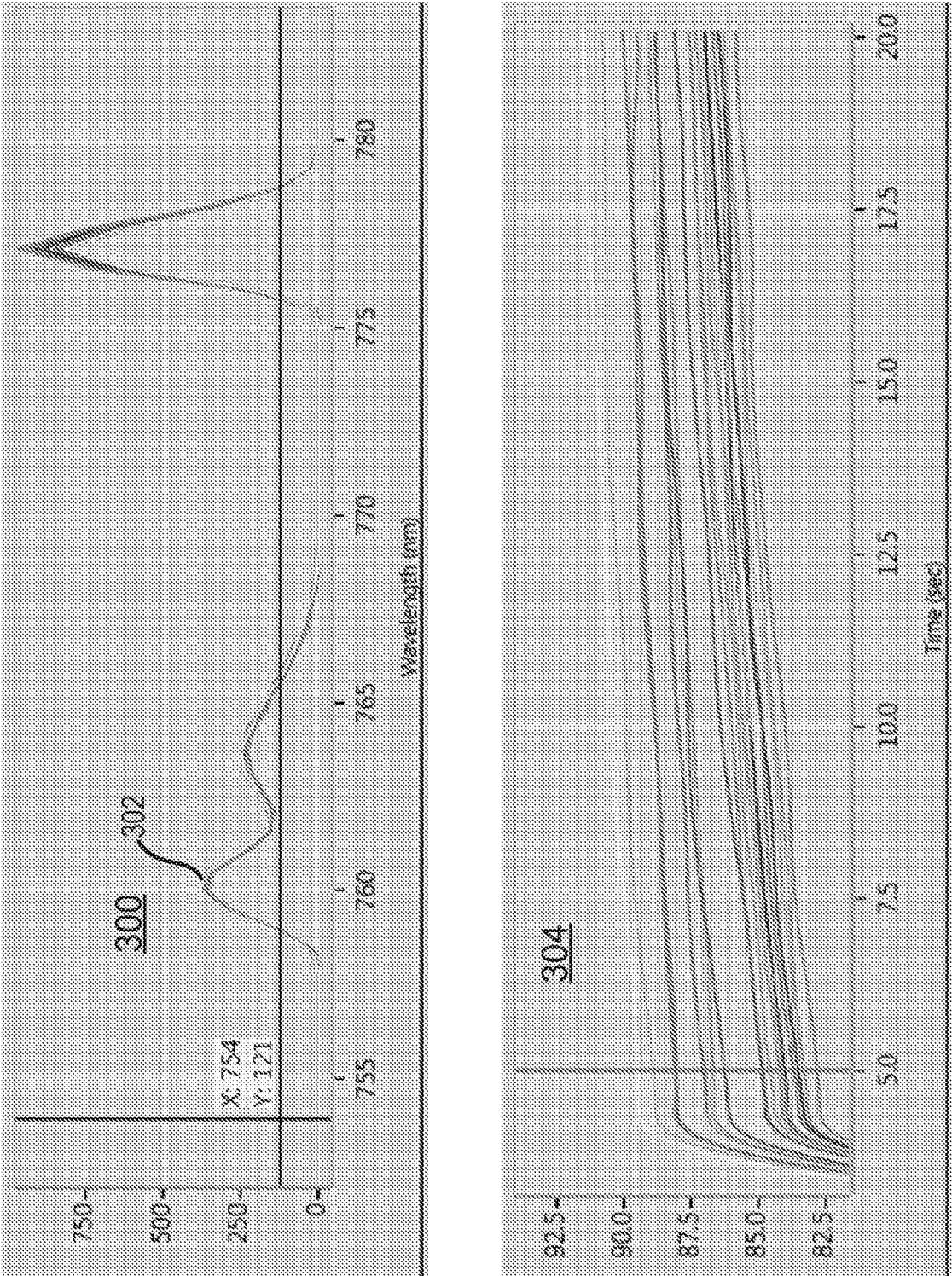


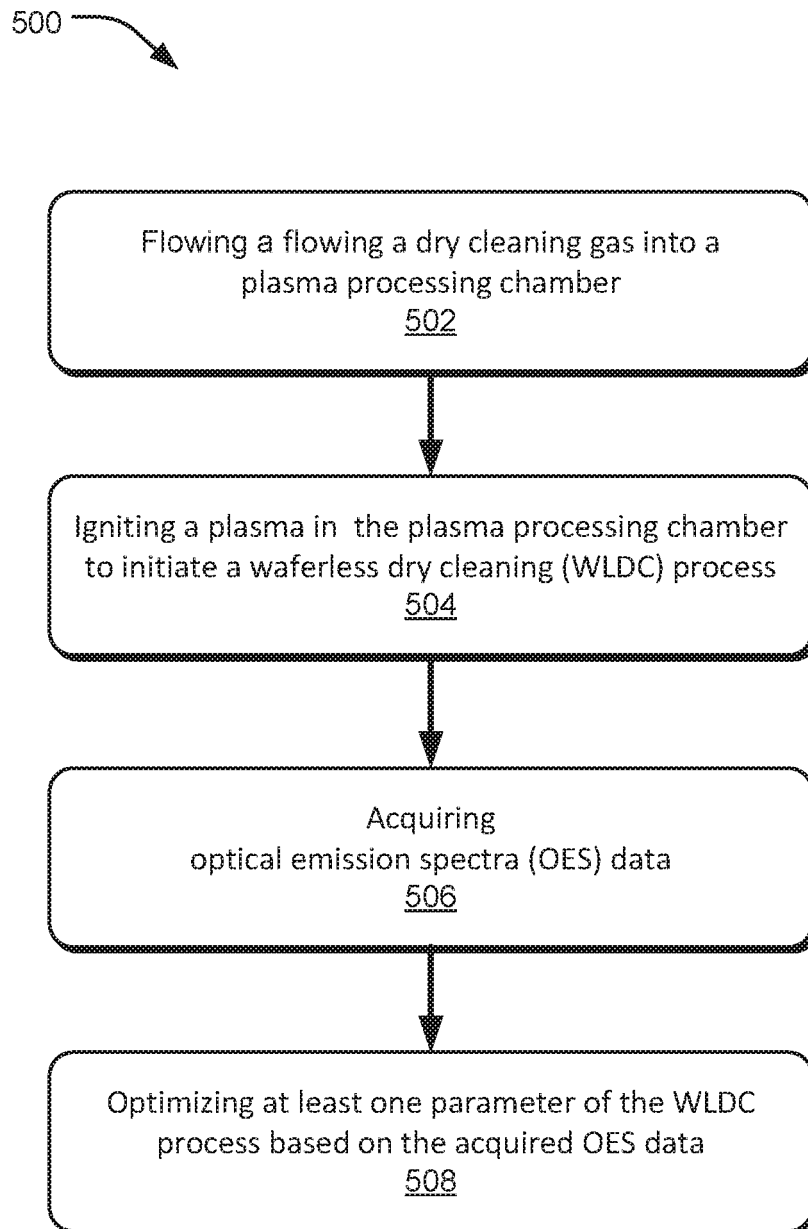
FIG. 3

400



Recipe	Step	Etch time	Press	Power [W]			DC	RDC		A-RDC		B.He Temp		ATCC
				HF	LF			[%]		C4F8	O2	C, E	Brine	
		[sec]	[mT]				[V]						{deg C }	[deg C]
WLDC-Via-4	O2 clean	20	400	200	0		0	50	1500	0	0	0	-10	25, 25
	<u>408</u>	<u>410</u>												
	N2 clean	10	200	700	0		0	50		0	0	0	-10	25, 25
									480					

FIG. 4

**FIG. 5**

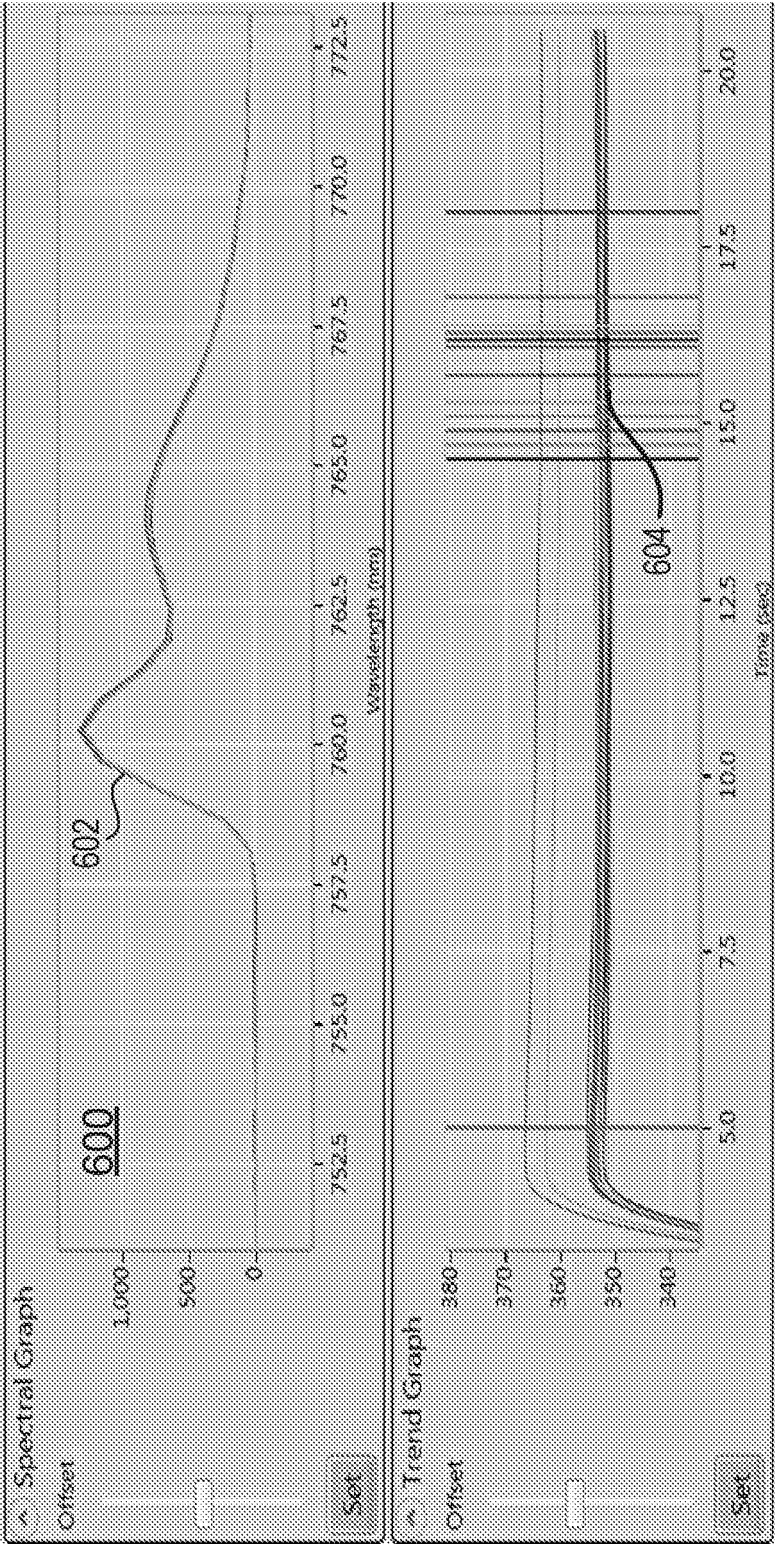
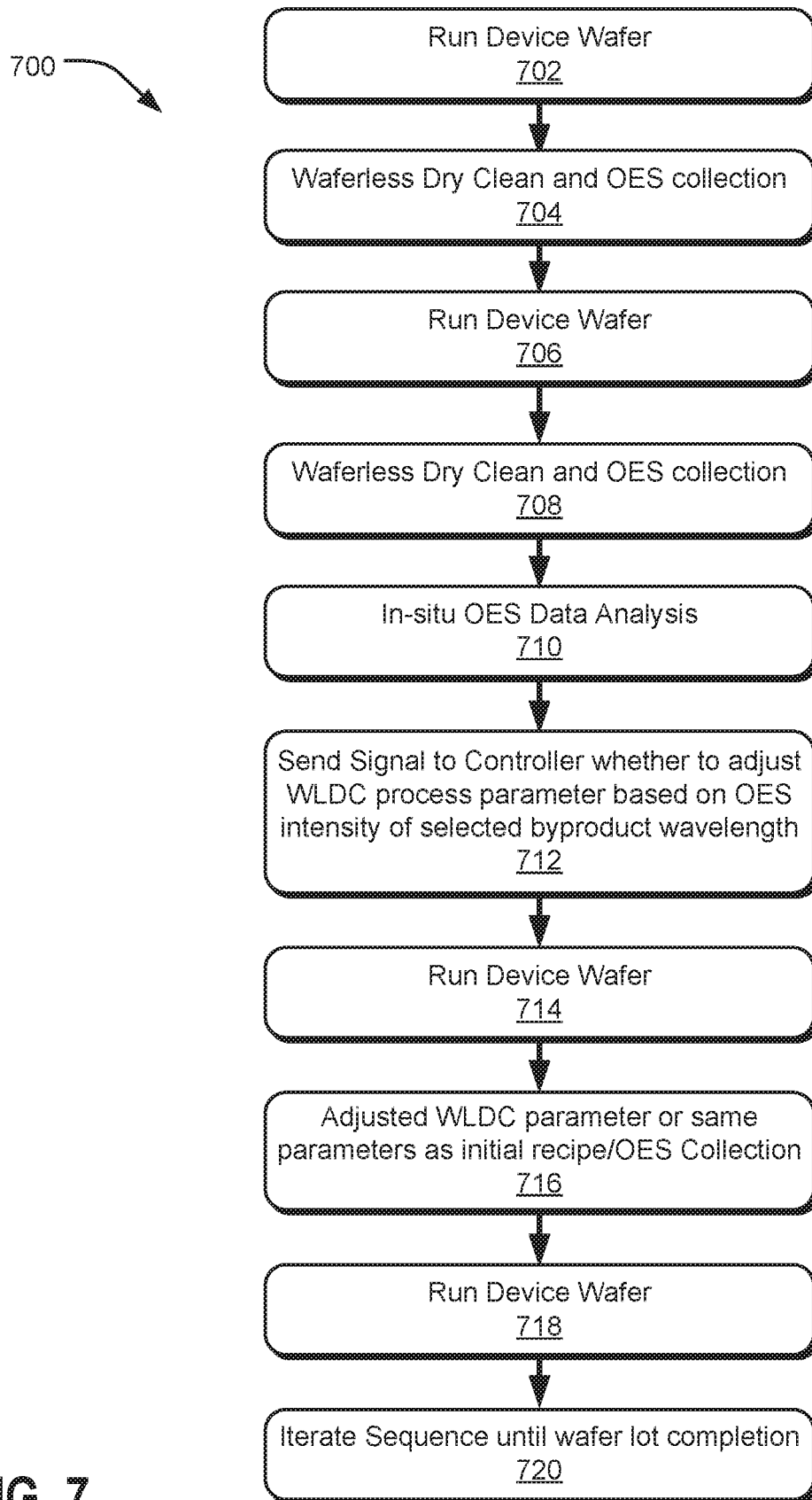


FIG. 6

**FIG. 7**